

Form PTO-1449

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PATENT AND TRADEMARK OFFICEATTY. - SUCKET NO.
MI22-1098PRIORITY SERIAL NO.
08/696,243LIST OF ART CITED BY APPLICANT
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Klaus F. SchuegrafPRIORITY FILING DATE
08/13/96PRIORITY GROUP
2813ICE49 U.S. PTO
09/21/2000

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
EK	AA	5,763,018	6/1998	Sato	438	790	
EK	AB	5,710,079	1/1998	Sukharev	438	778	
	AC	5,238,671	8/1993	Matson et al.	423	397	
	AD	5,610,105	3/1997	Vines et al.	437	238	
	AE	5,472,913	12/1995	Havemann et al.	437	238	
	AF	5,470,800	11/1995	Muroyama	437	238	
	AG	5,462,899	10/1995	Ikeda	437	238	
	AH	5,580,822	12/1992	Hayakawa et al.	437	187	
✓	AI	5,420,075	5/1995	Homma et al.	437	195	
EK	AJ	5,360,646	11/1994	Morita	427	574	

FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
AL	6349747	12/1994	Japan				
AM							
AN							
AO							
AP							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

EK	AR	IslamRaja, et al., "Two Precursor Model For Low-Pressure Chemical Vapor Deposition Of Silicon Dioxide From Tetraethylorthosilicate", J. Vac. Sci. Technol. B, Vol. 11, No. 3, May/Jun 1993, pp. 720-726.					
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EK	AS	Crowell, John E. et al., "The Chemical Vapor Deposition Of SiO ₂ From TEOS", Journal of Electron Spectroscopy And Related Phenomena, 54/55 (1990) pp. 1097-1104.					
EK	AT	Haupfear, E.A. et al., "Kinetics of SiO ₂ Deposition From Tetraethylorthosilicate", Electrochem. Soc. Vol. 141, No. 7, July 1994, pp. 1943-1950.					

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Erik Kulin

DATE CONSIDERED

6/14/00

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1098	PRIORITY SERIAL NO. 08/696,243
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U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
CK	AA	5,182,221	1/1993	Sato	437	67	
	AB						
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	AI						
	AJ						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL							
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	AN							
	AO							
	AP							

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CK	AR		Wolf, Stanley, "Silicon Processing for the VLSI Era", Vol. I, pp. 166-171				
			—	—			
CK	AS		"Hawley's Condensed Chemical Dictionary", 12th Ed., 1993, pg. 500				
	AT						

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Carl H. Koenig

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